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(54) Title (EN): FINE POWDER SPRAYING DEVICE

(54) Title (FR): PULVERISATEUR A POUDRE FINE

(54) Title (JA): 微粉体の散布装置

(57) Abstract:
(EN): A fine powder spraying device capable of spraying fine powder such as spacer for liquid crystal on a large-sized sprayed body without accompanying an increase in size of the device and without producing matters fallen on the sprayed body, comprising the sprayed body, spray nozzle pipes disposed apart a specified distance from each other and jetting the fine powder together with the flow of gas from the tip thereof to the sprayed body, a movement control means moving the sprayed body and the spray nozzle pipes three-dimensionally relative to each other, and a support part for the spray nozzle pipes and a support part for the sprayed body controlled by the movement control means. The spraying device is characterized in that the spray nozzle pipes are installed

on the outside of the plane of projection of the sprayed body in the upper vertical direction. The sprayed body is desirably formed so as to be rotated at a specified rotational speed by the support part therefore.

(FR): L'invention concerne un pulvérisateur à poudre fine permettant de pulvériser une poudre fine, tel qu'une couche d'espacement pour un dispositif à cristaux liquides, sur un corps de grande taille, sans augmenter les dimensions du dispositif et sans produire de matières sur le corps pulvérisé. L'ensemble comprend le corps pulvérisé, des tuyaux de buses de pulvérisation disposés à une distance spécifique les uns des autres et pulvérisant par leur extrémité la poudre fine avec un flux de gaz vers le corps, un moyen de commande des mouvements permettant de déplacer le corps pulvérisé et les tuyaux de buses de pulvérisation de façon tridimensionnelle l'un par rapport aux autres, ainsi qu'une partie de support pour les tuyaux de buses de pulvérisation et une partie de support pour le corps pulvérisé, commandés par le moyen de commande des mouvements. Le pulvérisateur se caractérise par le fait que les tuyaux de buses de pulvérisation sont installés sur l'extérieur du plan de projection du corps pulvérisé, dans la direction verticale ascendante. Le corps pulvérisé est conçu, de préférence, de façon à pouvoir être tourné à une vitesse de rotation spécifique par sa partie de support.

(JA): 本発明は、装置の大型化を伴わず、しかも被散布体上への落下物が生じることなしに、大型の被散布体上に液晶用スペーサなどの微粉体を散布することが可能な微粉体の散布装置を提供することを目的とする。 この目的を達成するために、本発明に係る微粉体の散布装置は、被散布体と所定間隔離間して配置され、前記被散布体に対してガス体の気流とともに微粉体をその先端から放出する散布ノズル管と、前記被散布体と前記散布ノズル管とを相対的に３次元的に移動させる移動制御手段と、この移動制御手段により制御される前記散布ノズル管の支持部並びに前記被散布体の支持部とを有する微粉体の散布装置であって、前記散布ノズル管が、前記被散布体の鉛直上方への射影面外に設置されてなることを特徴とする。なお、前記被散布体がその支持部により所定回転速度で回転するように構成されてなることが好ましい。

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